

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
)  
Shoji SETA, et al. ) Group Art Unit: *Not Yet Assigned*  
)  
Cont. of Application No.: 09/739,905 ) Examiner: *Not Yet Assigned*  
)  
Filed: Herewith )  
)  
For: DRY ETCHING METHOD AND )  
SEMICONDUCTOR DEVICE )  
MANUFACTURING METHOD )

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)**

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), Applicants bring to the attention of the Examiner the documents listed on the attached PTO-1449. Applicants file this Information Disclosure Statement together with the above-referenced continuation application.

Applicants previously submitted copies of the listed documents, or they were cited by the Examiner in prior application No. 09/739,905, filing date December 20, 2000, upon which Applicants rely for the benefits provided in 35 U.S.C. § 120. Applicants respectfully request that the Examiner consider the listed documents, and indicate that they were considered by making appropriate notations on the attached form.

The following documents are listed on the accompanying PTO-1449 and are in a non-English language. The statement of relevance, as indicated in the parent case, is the following:

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1. Japanese Patent Laid-Open (Kokai) No. 6-151302 discloses a method of removing high dose ion implantation resist by using ashing plasma including O<sub>2</sub>, CO, NO, or SO gas after wet etching.

2. Japanese Patent Laid-Open (Kokai) No. 10-172960 discloses a method of removing resist scum by using ashing plasma including O<sub>2</sub> gas.

3. Japanese Patent Laid-Open (Kokai) No. P2000-501573A discloses a method of resist removal by using ashing plasma including N or H gas with a discharge tube formed of sapphire.

In lieu of a statement of relevance or translation of non-English documents 1998-036950 and 10-125659, which appear on the attached PTO 1449, Applicants submitted an English language version of a Korean Patent Office Action in prior application No. 09/739,905, setting forth the relevance of those documents.

This submission does not represent that a search has been made or that no better art exists, and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the documents as prior art against any claim in the application and Applicants determine that the cited documents do not constitute "prior art" under United States law, Applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such documents.

Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

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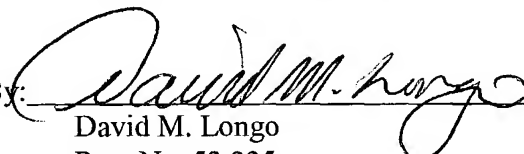
If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,  
GARRETT & DUNNER, L.L.P.

Dated: June 24, 2003

By:

  
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## INFORMATION DISCLOSURE CITATION

Atty. Docket No.	04329.2470-01	Cont. of Appln. No.	09/739,905
Applicant	Shoji SETA, et al.		
Filing Date	Herewith	Group:	Not Yet Assigned

## U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
	6,284,149	09/2001	Li et al.			
	6,312,874	11/2001	Chan et al.			
	6,168,726	01/2001	Li et al.			
	6,417,090	07/2002	Wang et al.			

## FOREIGN PATENT DOCUMENTS

Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
6-151302	05/1994	Japan			Abstract
10-172960	06/1998	Japan			Abstract
P2000-501573A	02/2000	Japan			Abstract
1998-036950	08/1998	Republic of Korea			No
10-125659	05/1998	Japan			No

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)


Examiner	Date Considered
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	
Form PTO 1449	Patent and Trademark Office - U.S. Department of Commerce